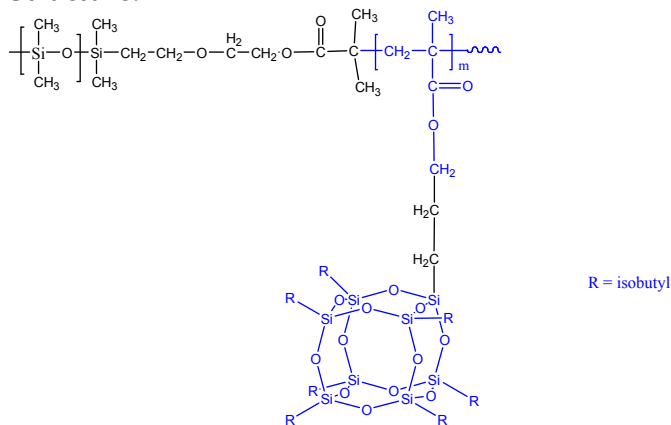


**Sample Name:****Poly(dimethylsiloxane-b-POSSisobutylmethacrylate)**

POSSisoButylMA: 3-(3,5,7,9,11,13,15-heptaisobutylpentacyclo[9.5.1.1<sub>3,9</sub>.1<sub>5,15</sub>.1<sub>7,13</sub>]octasiloxan-1-yl)propylmethacrylate

**Sample #: P14012-DMSPOSSisoBuMA****Structure:****Composition:**

Mn x 10 <sup>3</sup> PDMS-b- POSSisoBuMA	PDI
5.0-b-5.0	1.14

**Synthesis Procedure:**

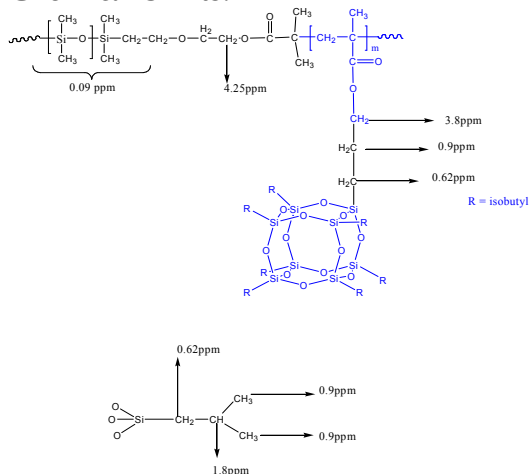
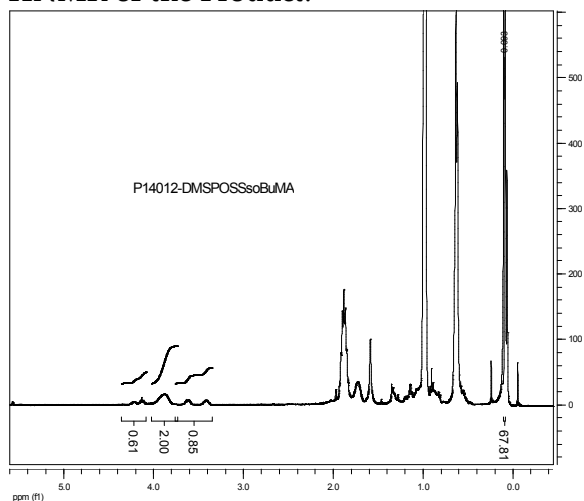
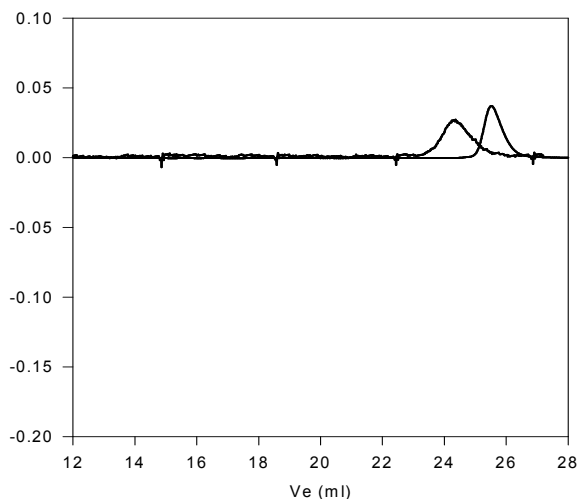
Polymer is synthesized by controlled radical polymerization process.

**Purification of the polymer:**

The obtained polymer dissolved in CHCl<sub>3</sub>/toluene and pass through the column packed with silica. The polymer was recovered by precipitation in cold ether/ethanol mixture.

**Solubility:**

Polymer is soluble in CHCl<sub>3</sub>, THF and toluene. The polymer precipitated out from hexane.

**Chemical Shifts:****HNMR of the Product:****SEC of the block copolymer:****P14012-DMSPOSSisoBuMA**

— Poly(DMS): M<sub>n</sub>=5000, M<sub>w</sub>=6300, M<sub>w</sub>/M<sub>n</sub>=1.05

— Block Copolymer PDMS(5000)-b-POSSisoBuMA(5,000), M<sub>w</sub>/M<sub>n</sub>=1.14

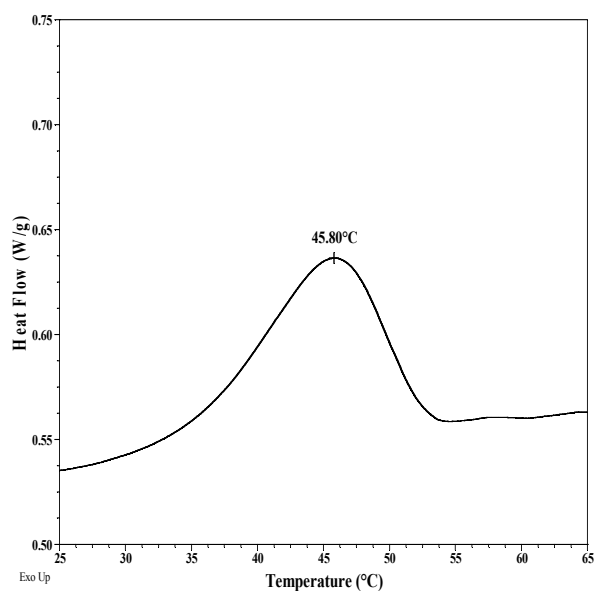
## Thermal analysis of the P14012-DMSPOSSisoBuMA

Thermal analysis of the samples was carried out on a TA Q100 differential scanning calorimeter at a heating rate of 10°C/min. The midpoint of the slope change of the heat flow plot of the second heating scan was considered as the glass transition temperature ( $T_g$ ).

### Melting and crystallization curve for the sample

The melting temperature ( $T_m$ ) was taken as the maximum of the endothermic peak where as the crystallization temperature ( $T_c$ ) was considered as the minimum of the exothermic peak.

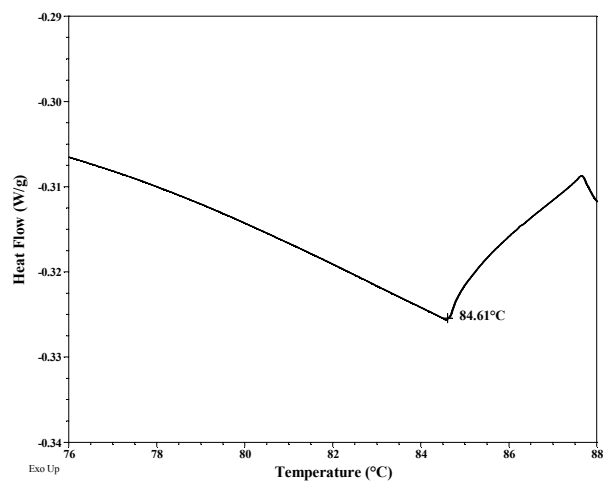
### Crystallization curves POSSMA block:



## Thermal analysis results at a glance:

Sample	$T_m$ (°C)	$T_c$ (°C)	$T_g$ (°C)
DMS block	-50	Not distinct	
POSSisoBuMA block	85	46	-

### Melting curves for POSMMA:



### Melting curve for DMS:

